Notice of Allowability	Application No.	Applicant(s)		
	10/676,224	HOWEY ET AL.	HOWEY ET AL.	
	Examiner	Art Unit		
	Patrick J Connolly	2877		
The MAILING DATE of this communication apperature All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in or other appropriate commu GHTŞ. This application is so	this application. If not include nication will be mailed in due	ded e course. THIS	
1. This communication is responsive to 27 May 2004.				
2. X The allowed claim(s) is/are <u>1-35</u> .				
3. \boxtimes The drawings filed on <u>30 September 2003</u> are accepted by	the Examiner.		•	
 4. ☐ Acknowledgment is made of a claim for foreign priority una) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	been received. been received in Application	n No	ation from the	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		a reply complying with the re	equirements	
5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give			NOTICE OF	
6. ☐ CORRECTED DRAWINGS (as "replacement sheets") mus (a) ☐ including changes required by the Notice of Draftspers 1) ☐ hereto or 2) ☐ to Paper No./Mail Date (b) ☐ including changes required by the attached Examiner's Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the state of the sheet of the state of the sheet	on's Patent Drawing Review s Amendment / Comment or 84(c)) should be written on the	in the Office action of e drawings in the front (not the R 1.121(d).		
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT 			Note the	
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☑ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Su	ormal Patent Application (PT Immary (PTO-413), Mail Date	⁻ O-152)	
 3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material 	8), 7. Examiner's a	Amendment/Comment Statement of Reasons for All TOTAL TOTAL TOTAL TOTAL TOTAL TOTAL TOTAL TOTAL	owance	

DETAILED ACTION

Allowable Subject Matter

Claims 1-35 allowed.

The following is an examiner's statement of reasons for allowance:

As to claim 1, the prior art of record, taken alone or in combination, fails to disclose or render obvious a wavemeter for a high repetition gas discharge laser including: an adjustable optic mounting containing an optic element having an assigned vertical optical plane in the wavemeter optical layout and comprising: a mounting dowel pin positioned on a platform holding the components of the wavemeter; a dowel receiving opening on the adjustable mirror mounting a tangent to which is in the assigned vertical optical plane, including the rest of the limitations of claim 1.

As to claim 2, the prior art of record, taken alone or in combination, fails to disclose or render obvious a wavemeter for a high repetition gas discharge laser including: an adjustable optic mounting containing an optic element, the optic element having an assigned vertical optical plane in the wavemeter optical layout and comprising: a tilt mechanism incorporated into the adjustable optic mounting enabling tilting the optic element about an axis in a plane parallel to a platform holding components of the wavemeter, including the rest of the limitations of claim 2.

As to claim 33, the prior art of record, taken alone or in combination, fails to disclose or render obvious a wavemeter for a high repetition gas discharge laser including: an optic mounting frame containing an optical diffusion element; a slit assembly containing a microslit adapted to selectively pass a slit of the optical output of the optical diffusion element to a succeeding optical element, moveably mounted to the optic mounting frame; a microslit position

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adjustment mechanism moving the slit assembly from a retracted position exposing the optic diffusion element for purposes of alignment to a down position with the slit aligned and moving the microslit into alignment, in combination with the rest of the limitations of claim 33.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Patrick J Connolly whose telephone number is 571.272.2412. The examiner can normally be reached on 9:00 am - 7:00 pm Monday-Thursday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Gregory J Toatley, Jr. can be reached on 571.272.2800 ext. 77. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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